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(71) Applicant(s):

NINGBO INLIGHT TECHNOLOGY LTD. [CN/CN]; Plant 7, Xiaowei Industrial Park, No. 399 Tianhai Road, Binhai New District Fenghua Economic and Technological Development Zone Ningbo, Zhejiang 315000 (CN) *(for all designated states)*

(72) Inventor(s):

MA, Daoyuan; Plant 7, Xiaowei Industrial Park, No. 399 Tianhai Road Binhai New District, Fenghua Economic and Technological Development Zone Ningbo, Zhejiang 315000 (CN)

GUO, Lingjie Jay; Plant 7, Xiaowei Industrial Park, No. 399 Tianhai Road Binhai New District, Fenghua Economic and Technological Development Zone Ningbo, Zhejiang 315000 (CN)

(74) Agent(s):

CHINA WISPRO INTELLECTUAL PROPERTY LLP.; Room A806, Zhongdi Building China University of Geosciences Base No.8 Yuexing 3rd Road, High-Tech Industrial Estate Nanshan District, Shenzhen, Guangdong 518057 (CN)

(54) Title (EN): PIGMENT MANUFACTURING METHOD

(54) Title (FR): PROCÉDÉ DE FABRICATION DE PIGMENT

(54) Title (ZH): 一种颜料的制造方法

(57) Abstract:

(EN): A pigment manufacturing method. The method comprises: providing a substrate; sequentially forming a plurality of stacked films on the substrate, wherein each film comprises a sacrificial layer and an optical film layer stacked in sequence, and the sacrificial layer is a release agent having stress or low stress; and performing film removal processing and pulverization processing on the plurality of formed films, and obtaining a pigment. The method, without increasing production costs, can prevent film layers from falling off irregularly during production, and thus prevent the production from being interrupted.

(FR): La présente invention concerne un procédé de fabrication de pigment. Le procédé comprend : la fourniture d'un substrat ; la formation séquentielle d'une pluralité de films empilés sur le substrat, chaque film comprenant une couche sacrificielle et une couche de film optique empilées en séquence, et la couche sacrificielle est un agent de libération ayant une contrainte ou une faible contrainte ; et la réalisation d'un traitement d'élimination de film et d'un traitement de pulvérisation sur la pluralité de films formés, et l'obtention d'un pigment. Le procédé, sans augmenter les coûts de production, peut empêcher des couches de film de tomber irrégulièrement pendant la production, et empêcher ainsi la production d'être interrompue.

(ZH): 一种颜料的制造方法,该方法包括:提供衬底;在衬底上依次形成叠加的多套薄膜,每套薄膜包括依次叠加的牺牲层和光学薄膜层,其中,牺牲层是具有应力或低应力的脱膜剂;对形成后的多套薄膜分别进行脱膜处理和粉碎处理,得到颜料。该方法能够在不增加生产成本的基础上,避免生产过程中膜层不规则脱落,从而避免生产中断。

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